



B. Patterning 분과

2021년 1월 28일(목), 09:00-10:30 / 채널 A

[TA1-B] Photolithography & Etching Technology

좌장: 유신재 교수 (충남대학교)

<p>TA1-B-1 09:00-09:30</p>	<p>[초청] 불소화 단분자 극자외선 레지스트 개발 이진균¹, 오현택¹, 우지훈¹, 김강현², 이상설² ¹인하대학교 고분자공학과, ²POSTECH 신소재공학과</p>
<p>TA1-B-2 09:30-10:00</p>	<p>[초청] Realistic 3D Profile Simulation Toward Next-generation High Aspect Ratio Etching Process Yeon Ho Im Jeonbuk National University</p>
<p>TA1-B-3 10:00-10:15</p>	<p>Influence of Additive Gases to Organic Chelators on Etch Characteristics of Copper Thin Films Using Inductively Coupled Plasma Reactive Ion Etching Eun Taek Lim, Mun Hwan Cha, Ji Soo lee, Sung Yong Park, and Chee Won Chung Department of Chemical Engineering, Inha University</p>